

Supplementary Information

Jingwei Bai, Suxian Huang, Leyu Wang, Yong Chen, Yu Huang*

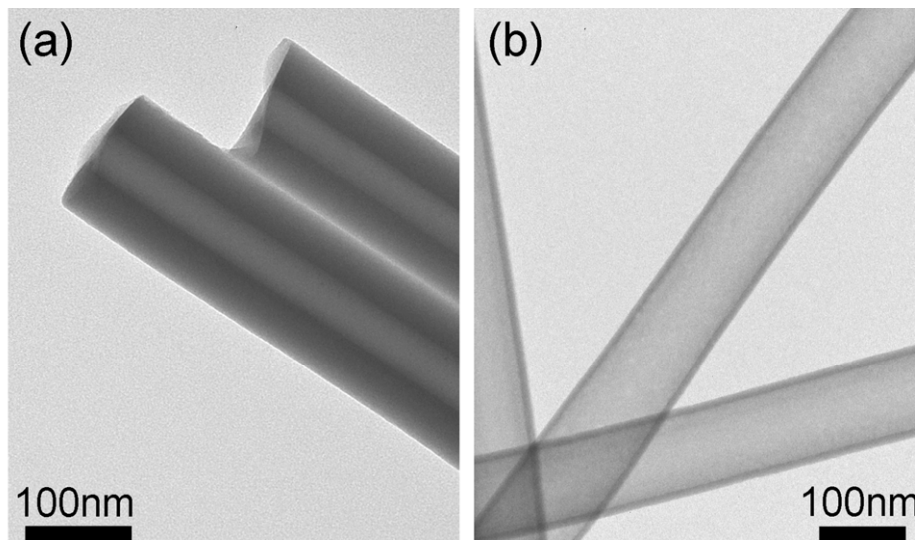


Figure S1. Transmission Electron Microscope images (JEM-1200 EX, JEOL) of silica nanotubes with inner diameter of 50nm (a) and 90nm (b) produced by oxidation of silicon nanowires followed by XeF_2 selective etching of Si core. The original wire diameter is around 100nm. The oxidation process was conducted at 900 °C in air for 150 minutes (a) and 6 minutes (b). XeF_2 etching was processed at etching pressure 3 torr at room temperature for 100s and cycled 10 times.